PE 4428

É UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:

Docket No.: ATMI-668 (7493)

Applicants:

RATH, Melissa K., et al.

4823

Application No.:

10/792,038

1752

Date Filed:

March 3, 2004

Examiner:

Conf. No.:

Art Unit:

LE, Hoa Van

Title:

COMPOSITION AND

PROCESS FOR POST-ETCH

REMOVAL OF

PHOTORESIST AND/OR SACRIFICIAL ANTI-REFLECTIVE MATERIAL

DEPOSITED ON A

SUBSTRATE

Customer No.: 24239

EXPRESS MAIL CERTIFICATE

I hereby certify that I am mailing the attached documents to the Commissioner for Patents on the date specified, in an envelope addressed to Mail Stop RCE, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 and Express Mailed under the provisions of 37 CFR 1.10.

Tristan Anne Fuierer

January 24, 2006

Date

EV 661 709 934 US

Express Mail Label Number

SUBMISSION OF POWER OF ATTORNEY AND STATEMENT UNDER 37 CFR 3.73(b); PRELIMINARY AMENDMENT; AND REQUEST FOR CONTINUED EXAMINATION IN UNITED STATES PATENT APPLICATION NO. 10/792,038

Mail Stop RCE Commissioner for Patents PO Box 1450 Alexandria, VA 22313-1450

Sir:

Prior to examination of the above-identified RCE patent application, please amend the claims, as set out in the following Section I (the Claims).

Remarks addressing the substance of the December 23, 2005 Advisory Action are set out in the Section II (Remarks) hereof.

TRI1\621358v1

2